L	Hits	Search Text	DB	Time stamp
Number				
-	0	substrate and "amorphous silicon" and	USPAT;	2004/09/16
		"optical layer" and reflect\$8 and (laser	US-PGPUB;	12:34
		near4 anneal\$4) and molten and crystal\$8	EPO; JPO;	
		and polysilicon	DERWENT	
_	73		USPAT;	2004/09/16
		optical and reflect\$8 and (laser near4	US-PGPUB;	12:35
		anneal\$4) and molten and crystal\$8 and	EPO; JPO;	
		polysilicon	DERWENT	1
_	2	substrate and "amorphous silicon" and	USPAT;	2004/09/16
		optical and reflect\$8 and (laser near4	US-PGPUB;	12:48
		anneal\$4) and molten and crystal\$8 and	EPO; JPO;	İ
		polysilicon and pattern\$8 and mask and	DERWENT	
		(anisotropic near4 etch) and (silicon	1	
		near4 nitride)		
-	94		USPAT;	2004/09/16
		optical and "silicon nitride" and	US-PGPUB;	12:49
		reflect\$8 and (laser near4 anneal\$4) and	EPO; JPO;	
		molten and crystal\$8	DERWENT	
-	54		USPAT;	2004/09/16
		optical and "silicon nitride" and	US-PGPUB;	12:49
		reflect\$8 and (laser near4 anneal\$4) and	EPO; JPO;	
		molten and crystal\$8 and polysilicon	DERWENT	
-	24	substrate and "amorphous silicon" and	USPAT;	2004/09/16
		optical and "silicon nitride" and	US-PGPUB;	12:50
		reflect\$8 and (laser near4 anneal\$4) and	EPO; JPO;	
		molten and crystal\$8 and polysilicon and	DERWENT	
		(pattern near4 mask)		
-	0	substrate and "amorphous silicon" and	USPAT;	2004/09/16
		optical and "silicon nitride" and	US-PGPUB;	12:51
		reflect\$8 and (laser near4 anneal\$4) and	EPO; JPO;	
		molten and crystal\$8 and polysilicon and	DERWENT	
		(pattern near4 mask) and "anisotropic		
		etch"		2004/00/16
-	7		USPAT;	2004/09/16
		optical and "silicon nitride" and	US-PGPUB;	12:52
		reflect\$8 and (laser near4 anneal\$4) and	EPO; JPO;	
		molten and crystal\$8 and polysilicon and	DERWENT	
	6	(pattern near4 mask) and "anisotropic"	IICDAM.	2004/09/16
1 -	ا م		USPAT;	1 ' '
		optical and "silicon nitride" and	US-PGPUB;	12:52
		reflect\$8 and (laser near4 anneal\$4) and	EPO; JPO; DERWENT	
		molten and crystal\$8 and polysilicon and (pattern near4 mask) and "anisotropic"	DEKMENT	
[(pattern near4 mask) and "anisotropic" and "silicon oxide"		
L		and sificot oxide	L	<u> </u>